



## EU Certification of Conformity

We,

Optogama, UAB  
Mokslininku st. 2A, LT-08412, Vilnius, LITHUANIA  
sales@optogama.com  
Phone: +370 5 219 4884

Declare that the DoC is issued under our sole responsibility and belongs to the following product:

<b>Apparatus model / Product</b>	<b>LPA-Av2</b>
<b>Type</b>	<b>Advanced laser power attenuator</b>

Object of declaration:



The object of the declaration described above is in conformity with the relevant Union harmonization legalization:

<b>Electromagnetic disturbances:</b>	
Radiated disturbance	EN 55011:2016 EN 55011:2016/A1:2017
<b>Electromagnetic immunity:</b>	
Electrostatic discharge immunity test	EN 61000-6-1:2007 EN 61000-4-2:2009
Radiated RF electromagnetic field immunity test	EN 61000-6-1:2007 EN 61000-4-3:2006 EN 61000-4-3:2006/A1:2008 EN 61000-4-3:2006/A2:2010
Immunity to conducted radio frequency electromagnetic disturbances (signal lines)	EN 61000-6-1:2007 EN 61000-4-6:2014



REFERENCES AND TITLES OF THE STANDARDS

EN 55011:2016

Industrial, scientific and medical equipment - Radio-frequency disturbance characteristics - Limits and methods of measurement (CISPR 11:2015).

Amendment EN 55011:2016/A1:2017.

EN 61000-6-1:2007

Electromagnetic compatibility (EMC) - Part 6-1: Generic standards - Immunity standard for residential, commercial and light-industrial environments (IEC 61000-6-1:2016).

EN 61000-4-2:2009

Electromagnetic compatibility (EMC) - Part 4-2: Testing and measurement techniques - Electrostatic discharge immunity test (IEC 61000-4-2:2008).

EN 61000-4-3:2006

Electromagnetic compatibility (EMC) - Part 4-3: Testing and measurement techniques - Radiated, radio-frequency, electromagnetic field immunity test (IEC 61000-4-3:2006).

Amendment EN 61000-4-3:2006/A1:2008.

Amendment EN 61000-4-3:2006/A2:2010.

EN 61000-4-6:2014

Electromagnetic compatibility (EMC) -- Part 4-6: Testing and measurement techniques - Immunity to conducted disturbances, induced by radio-frequency fields (IEC 61000-4-6:2013).

Vilnius, 2019-03-20



Tadas Lipinskas, CEO